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SHEET 1 OF 2 ORMATION DISCLOSURE ATTY. DOCKET NO. SERIAL NO. 055071-0328 10/756,829 CITATION IN AN APPLICATION **APPLICANT** Robert John SOCHA, et al. FILING DATE **GROUP** (PTO-1449) 2825 January 14, 2004 **U.S. PATENT DOCUMENTS** EXAMINER'S CITE **Document Number Publication Date** Name of Patentee or Applicant of Cited Pages, Columns, Lines, Where INITIALS MM-DD-YYYY **Document** Relevant Passages or Relevant Number-Kind Code2 (# known) Figures Appear 07/02/2002 Stanton 6,413,684 B1 SM US 6,355,382 B1 03/12/2002 Yasuzato et al. ÜS 5,229,230 07/20/1993 Kamon UŞ 5,895,741 04-20-1999 Hasegawa et al. US 6,214,497 B1 04-10-2001 Stanton US 2002/0152452 A1 10-17-2002 Socha ŪS 5,682,323 10-28-1997 Pasch et al. US 6,303,253 B1 10-16-2001 Lu US 6,223,139 B1 04-24-2001 Wong et al. US 6,777,141 08-2004 Pierrat, Christophe US 6,787,271 09-2004 Cote et al. US 2002/0083410 06-2002 Wu et al. Shi et al. US 6.792,591 09-2004 US 02-2003 6,519,760 Shi et al. Hau et al. US 2003/0228541 12-2003 US 2002/0157081 10-2002 Shi et al. 10-2004 US 6.807.662 Toublan et al. Adam, Konstantinos 2004/0122636 06-2004 US FOREIGN PATENT DOCUMENTS **EXAMINER'S** Foreign Patent Document Publication Date Name of Patentee or Pages, Columns, Lines Translation INITIALS Country Codes-Number 4-Kind Applicant of Cited Document Where Relevant MM-DD-YYYY CITE Yes No Codes (if known) Figures Appear OTHER ART (Including Author, Title, Date, Pertinent Pages, Etc.) **EXAMINER'S** Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, INITIALS journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where CITE published. NO. **EXAMINER** DATE CONSIDERED

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